

- **Thin Film Annealing**
 - Backend Vacuum Annealing Furnace

Annealing Library

- No element of III-V group.
- Low volatility.
- Each sample should not smaller than one quarter of 6 or 4 inches.

High Vacuum Mode

- Ambient : O₂ or N₂
- Temperature : RT ~ 600°C
- Maximum gas flow rate : O₂ (30 sccm) and N₂ (120 sccm)

Low Pressure Mode

- Pressure about : 10⁻⁷ torr
- Temperature : RT ~ 600°C